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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 66302-006US1	Application No. 10/536,512	
(Use several sheets if necessary)		Applicant Jae-Hyun Kim		
		Filing Date May 25, 2005	Group Art Unit 1752	
(37 CFR §1.98(b))				

			U.S. Pate	ent Documents			
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
/SL/	AA	6,033,830	03/07/2000	Sinta et al.	430	325	
	AB						
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	Foreign Patent Documents or Published Foreign Patent Applications							
		Country or			Translation			
Initial	ID	Number	Date	Patent Office	Class	Subclass	Yes	No
/SL/	AL	WO00/54105	09/14/2000	WIPO				
	AM							
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	AO							
	AP							

Other Documents (include Author, Title, Date, and Place of Publication)					
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/SL/	AQ	Hwang S-H et al., "A novel organic bottom anti-reflective coating material for 193nm excimer lases lithography," Polymer, Elsevier Science Publishers B.V, GB, Vol. 41, No 17, August 2000 (2000-08), pages 6691-6694, XP004196891.			
	AR				
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